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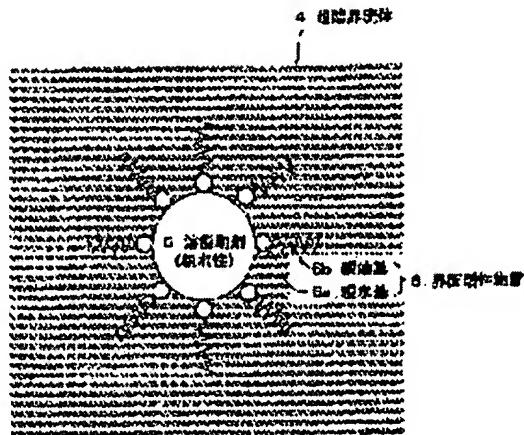
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**(54) SURFACE TREATMENT METHOD****(57)Abstract:**

**PROBLEM TO BE SOLVED:** To provide a surface treatment method which can surely eliminate residue by only treatment using supercritical fluid.

**SOLUTION:** In the surface treatment method wherein a surface on which a structure is formed is treated by the supercritical fluid 4, ammonium hydroxide, alkanolamine, amine fluoride, hydrofluoric acid, etc., are added as solubilizer 5 to the supercritical fluid 4. A surfactant 6 may be added to the supercritical fluid 4 together with a solubilizer 5. A polar solvent may be used as the surfactant 6.

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